

**Amendments to the Claims:**

This listing of claims will replace all prior versions, and listings, of claims in the application:

**Listing of Claims:**

1. - 9. (Canceled).

10. (Currently Amended) A pattern writing system comprising:

a plurality of mirror device devices each including micromirrors arranged two-dimensionally,

a plurality of light sources ~~source~~ for each supplying exposure light to said mirror device devices,

a substrate for mask pattern writing,

a moving mechanism for moving said substrate in X- and Y-directions,

means for directly projecting or reduction-projecting each of patterns output from said mirror device devices onto said substrate, and

control means for overlapping each of said projection patterns a plurality of times over the substantially whole surface of a pattern projection area on said substrate to thereby perform exposure,

~~a plurality of said wavelength conversion solid state lasers,~~

~~a plurality of said mirror devices, and~~

~~means for averaging output lights of at least two of said plurality of wavelength-conversion solid state lasers and supplying the average light to said mirror devices, respectively,~~

~~wherein a wavelength conversion solid state laser or a microwave excited excimer laser is used as said light source, and~~

~~wherein said means for averaging said output lights and supplying the average light to said mirror device/devices comprises a polarization beam splitter~~

~~wherein the plurality of the light sources each generate a wavelength-conversion solid-state laser or a copper vapor laser,~~

~~wherein an optically averaging system is arranged between the plurality of the light sources and the plurality of the mirror devices so as to average output lights of at least two of~~

said plurality of the wavelength-conversion solid-state lasers or the copper vapor lasers to supply averaged lights to said mirror devices, and

wherein said control means is operable to partially overlap the patterns from the mirror devices the plurality of times to realize a level of gradations determined by overlapped times of the spots.

11. (Canceled).

12. (Currently Amended) A pattern writing system according to claim 10, wherein ~~a second harmonic of a solid-state laser or a copper vapor laser is used as said light source, and the system further comprising a wavelength conversion element for converting a wavelength of said projection light the plurality of the light sources each generate a second harmonic of the wavelength-conversion solid-state laser or the copper vapor laser.~~

13. - 23. (Canceled).

24. (Previously Presented) A pattern writing system including a pulse laser light generating portion and two-dimensionally arranged micromirrors and reduction-projecting said micromirrors onto a substrate, said pattern writing system comprising:

means for generating pulse laser light;

means for performing pattern transfer while overlapping, in both of two perpendicular moving directions on said substrate, projection patterns of said two-dimensionally arranged micromirrors, each projected onto said substrate by one-time pulse laser light; and

a pinhole plate that can divide, into a large number of fine light beams, the pulse laser light from the pulse light source applied to a mirror device including said micromirrors,

wherein said pinhole plate has a first Peltier element provided on one side of a first surface and a second Peltier element provided on another side of the first surface opposite the one side.

25 - 31. (Canceled).